

CALL FOR PAPERS

Journal of Microelectronic Manufacturing (JoMM) Special Issue on **Materials**

Guest Editor Mark Neisser



Dr. Mark Neisser worked as the Resist and Materials Research Manager at SEMATECH in where he led a team that did research into expanding current EUV resist material platforms and researching new solutions such as metal based resist. He earned his Bachelor's degree at Cornell University and his Master's and Ph.D. degrees at the University of Michigan, Ann Arbor, all in Chemistry. Dr. Neisser worked at IBM for sixteen years where he focused on packaging materials and semiconductor lithography research, followed by positions managing research and development of photoresists and of ancillary materials for lithography at Arch and at AZ Electronic Materials, respectively. He is the author of over three dozen patents and 100 technical publications and is the inventor of double exposure as a resolution enhancement for lithography. Dr. Neisser is the current chair of the International Roadmap for Devices and Systems (IRDS) Lithography Technical Working Group.

Topic: **Materials that boost advanced IC manufacturing**

“Almost every process inside a semiconductor fab relies on both sophisticated tools and sophisticated materials. In this special issue we want to highlight a diverse set of materials that are examples of how chemistry can provide new options for Fab engineers. The materials can be ones that improve existing processes, one that support the introduction of new processes, or ones that make it possible to implement new approaches to chip manufacturing. Papers should describe what the material is, what its use is and describe some scientific study related to the material or materials in question”.

Scope:

- Photoresist Materials
- Self-assembling Materials
- Antireflection Coatings
- Packaging Materials
- Other Materials Related to Advanced Semiconductor Processing

Submission Information:

- Papers targeting the special issue should be submitted through the JoMM submission system (<http://jommpublish.org/>) or sent by email (jomm@jommpublish.org), and will undergo a similar review process as regularly submitted papers.
- Deadline for submission is October 30th, 2020.
- Manuscript length and format info is available at the website.

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